

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S219	2139	257/412,757,766.ccls. and @ad<"20040301"	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2007/10/19 17:03
S220	1598	257/412,757.ccls. and @ad<"20040301"	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2007/10/28 15:37
S221	1066	257/412,757.ccls. and @ad<"20040301"	US-PGPUB; USPAT; USOCR	OR	ON	2007/10/28 20:22
S222	39	("3252003" "3290127" "3463971" "3472712").PN. OR ("3590471").URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/10/28 16:03
S223	719	257/766,768.ccls. and @ad<"20040301"	US-PGPUB; USPAT; USOCR	OR	ON	2007/10/28 17:44
S224	1711	257/e21.438,e21.439.ccls. and @ad<"20040301"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; IBM_TDB	OR	ON	2007/10/28 17:44
S225	8	("3873373" "4616399" "4728617").PN. OR ("4833097").URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/10/28 19:23
S226	50954	gate adj oxide	US-PGPUB; USPAT; USOCR	OR	OFF	2007/10/28 19:24
S227	65845	gate adj oxide	US-PGPUB; USPAT; USOCR; FPRS; EPO; DERWENT; IBM_TDB	OR	ON	2007/10/28 19:24
S228	211	silicided adj gate adj electrode	US-PGPUB; USPAT; USOCR; FPRS; EPO; DERWENT; IBM_TDB	OR	ON	2007/10/28 19:25

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S22 9	66504	polysilicon adj (material layer film)	US-PGPUB; USPAT; USOCR; FPRS; EPO; DERWENT; IBM_TDB	OR	ON	2007/10/28 19:25
S23 0	1365	alloy near6 (first adj metal and second adj metal)	US-PGPUB; USPAT; USOCR; FPRS; EPO; DERWENT; IBM_TDB	OR	ON	2007/10/28 19:34
S23 1	265794	anneal\$3	US-PGPUB; USPAT; USOCR; FPRS; EPO; DERWENT; IBM_TDB	OR	ON	2007/10/28 19:27
S23 2	171202	patterning	US-PGPUB; USPAT; USOCR; FPRS; EPO; DERWENT; IBM_TDB	OR	ON	2007/10/28 19:27
S23 3	6831034	source/drain s/d drain/source d/s source?drain drain?source source near2 drain	US-PGPUB; USPAT; USOCR; FPRS; EPO; DERWENT; IBM_TDB	OR	ON	2007/10/28 19:30
S23 4	6831034	(source/drain s/d drain/source d/s source?drain drain?source source near2 drain)	US-PGPUB; USPAT; USOCR; FPRS; EPO; DERWENT; IBM_TDB	OR	ON	2007/10/28 19:30
S23 5	10151	S227 S229	US-PGPUB; USPAT; USOCR; FPRS; EPO; DERWENT; IBM_TDB	WITH	ON	2007/10/28 19:33

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S23 6	2515	alloy with (first adj metal and second adj metal)	US-PGPUB; USPAT; USOCR; FPRS; EPO; DERWENT; IBM_TDB	OR	ON	2007/10/28 19:36
S23 7	33034	(first adj metal and second adj metal)	US-PGPUB; USPAT; USOCR; FPRS; EPO; DERWENT; IBM_TDB	OR	ON	2007/10/28 19:37
S23 8	44759	(first adj metal withsecond adj metal)	US-PGPUB; USPAT; USOCR; FPRS; EPO; DERWENT; IBM_TDB	OR	ON	2007/10/28 19:37
S23 9	25049	(first adj metal with second adj metal)	US-PGPUB; USPAT; USOCR; FPRS; EPO; DERWENT; IBM_TDB	OR	ON	2007/10/28 19:38
S24 0	10154	S235 S239 with S228	US-PGPUB; USPAT; USOCR; FPRS; EPO; DERWENT; IBM_TDB	OR	ON	2007/10/28 19:39
S24 1	0	S235 S239 S228	US-PGPUB; USPAT; USOCR; FPRS; EPO; DERWENT; IBM_TDB	WITH	ON	2007/10/28 19:39
S24 2	0	S235 S239 S228	US-PGPUB; USPAT; USOCR; FPRS; EPO; DERWENT; IBM_TDB	SAME	ON	2007/10/28 19:39

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S24 3	4	S235 S239 S228	US-PGPUB; USPAT; USOCR; FPRS; EPO; DERWENT; IBM_TDB	AND	ON	2007/10/28 19:39
S24 4	14	("5796166" "5827762" "5849616" "5949092" "6130123" "6166417"). PN. OR ("6534837").URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/10/28 19:57
S24 5	24	("3936860" "4555842" "5559351" "5796166" "5834353" "5912509" "5945821" "5973363").PN. OR ("6166417").URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/10/28 20:06
S24 6	35	S244 S245	US-PGPUB; USPAT; USOCR	OR	OFF	2007/10/28 20:07
S24 7	17	S246 and silicide	US-PGPUB; USPAT; USOCR	OR	OFF	2007/10/28 20:07
S24 8	183	438/581,583.ccls. and @ad<"20040301"	US-PGPUB; USPAT; USOCR	OR	ON	2007/10/28 20:28
S24 9	337	438/630,651.ccls. and @ad<"20040301"	US-PGPUB; USPAT; USOCR	OR	ON	2007/10/28 20:32
S25 0	11	gate adj oxide and polysilicon and alloy and first adj metal and second adj metal and silicid\$3 adj gate adj electrode and anneal\$3 and source and drain and (subsequent before after follow\$3).clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2007/10/28 20:36

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Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L30	11	gate adj oxide and polysilicon and alloy and first adj metal and second adj metal and silicid\$3 adj gate adj electrode and anneal\$3 and source and drain and (subsequent before after follow\$3).clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2007/10/28 20:36